

Supporting Information

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Phosphorus-containing polymers from tetrakis(hydroxymethyl)phosphonium sulfate. III. A new hydrolysis-resistant tris(allyloxymethyl)phosphine oxide and its thiol-ene reaction under ultraviolet irradiation

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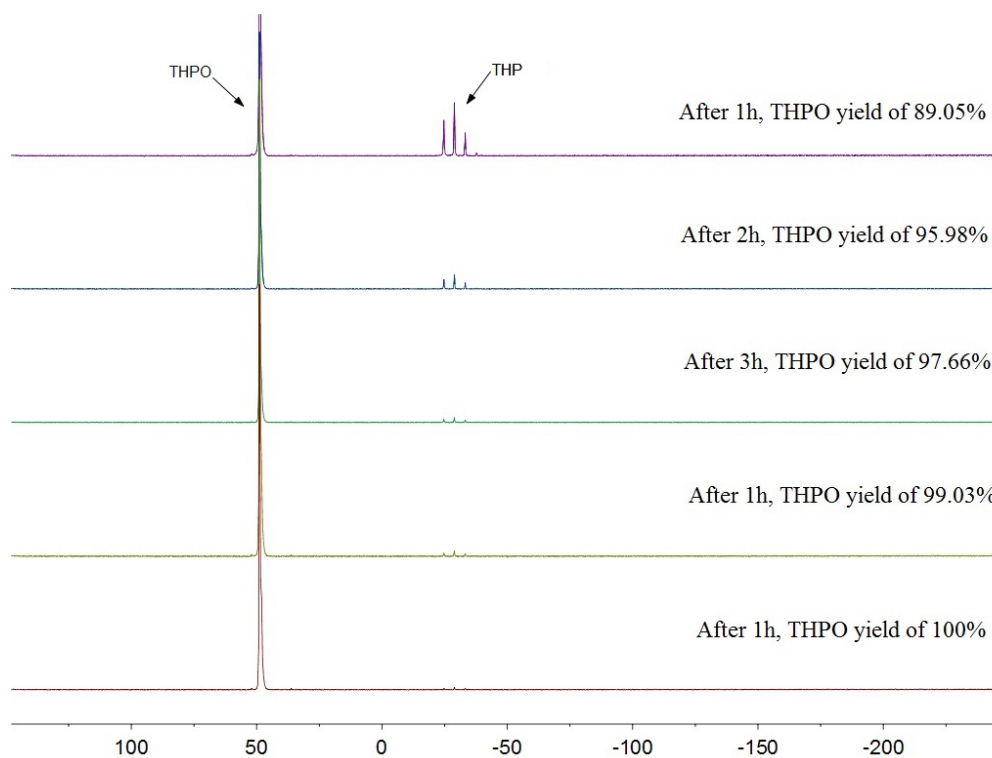


Figure S1. ³¹P NMR spectrum of reaction mixture at one hour interval.